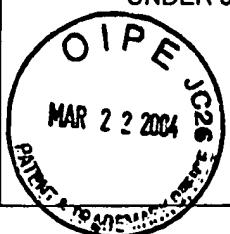


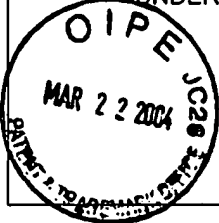
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE		ATTORNEY DOCKET NO.:	SERIAL NO.:
INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR §1.56, §1.97, and §1.98 PTO-1449 FORM Sheet 1 of 4		38203-6080C	10/727,081
		APPLICANTS:	
		Smith et al.	
		FILING DATE:	GROUP ART UNIT:
		12/02/2003	Unknown <i>2851</i>

U.S. PATENT DOCUMENTS						
† EX'R INITIAL	*REF. #	PATENT NUMBER	DATE	NAME	U.S. CLASS/ SUBCLASS	FILING DATE (If appropriate)
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	B*	5,285,236	02/08/94	Jain	355/53	09/30/92
	C*	5,402,224	3/28/95	Hirukawa <i>et al.</i>	356/124	9/24/93
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	E*	5,615,006	3/25/97	Hirukawa <i>et al.</i>	356/124	6/6/95
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	G*	5,877,861	3/2/99	Ausschnitt <i>et al.</i>	356/401	11/14/97
	H*	5,894,350	4/13/99	Hsieh <i>et al.</i>	356/399	6/12/98
	I*	6,079,256	06/27/00	Bareket	73/105	12/07/98
	J*	6,143,621	11/07/00	Tzeng <i>et al.</i>	438/401	06/14/99
	K*	6,259,525	7/10/01	David	356/399	2/24/00

FOREIGN PATENT DOCUMENTS				
† EX'R INITIAL	*REF. #			TRANSLATION (YES/NO)
		NONE		

OTHER DOCUMENTS		
† EX'R INITIAL	*REF. #	CITATION (Author, Article Title, Journal/Book Title, Date, Pertinent Pages, etc.)
<i>USA</i>	L*	Armitage Jr., J.D. and Kirk, J.P., "Analysis of overlay distortion patterns", <i>SPIE</i> , 921:207-222, (1988)
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EXAMINER'S SIGNATURE <i>Calvin L. G.</i>	DATE CONSIDERED <i>2/22/05</i>
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		APPLICANTS: Smith et al.	
Sheet 2 of 4		FILING DATE: 12/02/2003	GROUP ART UNIT: Unknown <i>2851</i>

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	R*	Dooley, T. and Yang, Y., "Stepper matching for optimum line performance", <i>SPIE</i> , <u>3051</u> :426-432, (1997)
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	AD*	Mc Fadden, E.A. and Ausschnitt, C.P., "A Computer Aided Engineering Workstation For Registration Control", <i>SPIE</i> , <u>1087</u> :255-266, (1989)

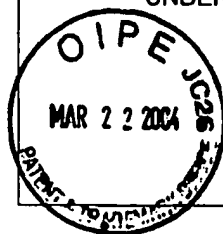
EXAMINER'S SIGNATURE <i>Colin H. S.</i>	DATE CONSIDERED <i>2/22/05</i>
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INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR §1.56, §1.97, and §1.98 PTO-1449 FORM Sheet 3 of 4		APPLICANTS: Smith et al.	
		FILING DATE: 12/02/2003	GROUP ART UNIT: Unknown <i>2857</i>

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	AF*	Newnam, B.E. and Viswanathan, V.K., "Development of XUV projection lithograph at 60-80 nm", <i>SPIE</i> , <u>1671</u> :419-436, (1992)
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	AL*	Raugh, M.R., "Error estimation for lattice methods of stage self-calibration", <i>SPIE</i> , <u>3050</u> :614-625, (1997)
	AM*	Sullivan, N.T., "Semiconductor Pattern Overlay", <i>SPIE Critical Reviews of Optical Science and Technology</i> , <u>CR52</u> :160-188, (1994)
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	AS*	van den Brink <i>et al.</i> , "New 0.54 Aperture i-Line Wafer Stepper With Field By Field Leveling Combined With Global Alignment", <i>SPIE</i> , <u>1463</u> :709-724, (1991)

EXAMINER'S SIGNATURE <i>Carl J. M. 51</i>	DATE CONSIDERED <i>2/22/05</i>
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		APPLICANTS:	
		Smith et al.	
		FILING DATE:	GROUP ART UNIT:
		12/02/2003	Unknown <i>2851</i>



<i>CS</i>	AT*	van Schoot <i>et al.</i> , "0.7 NA DUV Step & Scan System For 150nm Imaging With Improved Overlay", <i>SPIE</i> , 3679:448-463, (1999)
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	AW*	Zavec, T.E., "Machine Models and Registration", <i>SPIE Critical Reviews of Optical Science and Technology</i> , CR52:134-159 (1994).

EXAMINER'S SIGNATURE	<i>Al. L. H. S.</i>	DATE CONSIDERED	<i>2/22/05</i>
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